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Notice of Allowability	Application No.	Applicant(s)	
	10/762,031 ·	YUEH ET AL	
	Examiner	Art Unit	
	John S. Chu	1752	
The MAILING DATE of this communication appe All claims being allowable, PROSECUTION ON THE MERITS IS herewith (or previously mailed), a Notice of Allowance (PTOL-85) NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT RI of the Office or upon petition by the applicant. See 37 CFR 1.313	(OR REMAINS) CLOSED in to or other appropriate commun GHTS. This application is sul	his application. If not included ication will be mailed in due co	urse THIS
1. This communication is responsive to 8/26/05.			¥
2. The allowed claim(s) is/are <u>1-8</u> .			
 3.	been received. been received in Application cuments have been received in Application of this communication to file a lENT of this application. itted. Note the attached EXAN as reason(s) why the oath or do to be submitted. ion's Patent Drawing Review (as Amendment / Comment or in leading to 37 CFR is it of BIOLOGICAL MATER	No In this national stage application reply complying with the requinities. AMENDMENT or NO eclaration is deficient. PTO-948) attached In the Office action of drawings in the front (not the ball-1.121(d). RIAL must be submitted. No	rements FICE OF
Attachment(s) 1. Notice of References Cited (PTO-892) 2. Notice of Draftperson's Patent Drawing Review (PTO-948) 3. Information Disclosure Statements (PTO-1449 or PTO/SB/0 Paper No./Mail Date 4. Examiner's Comment Regarding Requirement for Deposit of Biological Material	6. ☐ Interview Sun Paper No./M 8), 7. ☐ Examiner's A	rmal Patent Application (PTO- nmary (PTO-413), ail Date mendment/Comment ratement of Reasons for Allowa	

REASONS FOR ALLOWANCE

1. The following is an examiner's statement of reasons for allowance: The claimed invention is drawn to the following:

1 (Currently Amended). A method comprising:

forming a photoresist by attaching a photoactive compound including

diazonaphthoquinone to a polymer backbone; and

exposing said photoresist to extreme ultraviolet radiation.

The claimed invention is interpreted to be a method of forming a photoresist wherein the term "attaching...to a polymer backbone" has the meaning of being actually being on the polymer backbone to where a polymerization process is required to put the diazonaphthoquinone on the backbone. This definition is taken from the specification Fig. 1 and page 5, lines 11-22 and if seen in this light, none of the prior art references of record anticipate or render obvious the claimed method because the diazonaphthoquinone in the prior art is condensed onto a pendant group, namely hydroxystyrene in the case of WEST et al, OBERLANDER et al (5,866,295), McCULLOUGH et al (6,218,083) and ISHIZUKA et al (6,824,947).

Because none of the prior art references anticipate or render obvious the claimed invention, claims 1-8 are seen as allowable and passed to issue.

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

2. The drawing filed January 21, 2004 has been accepted by the examiner.

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3. Any inquiry concerning this communication or earlier communications from the

examiner should be directed to Examiner Chu whose telephone number is (571) 272-1329. The

examiner can normally be reached on Monday - Friday from 9:30 am to 6:00 pm.

The fax phone number for the USPTO is (571) 273-8300.

Any inquiry of a general nature or relating to the status of this application or proceeding

should be directed to the Group receptionist whose telephone number is (571) 272-1700.

Information regarding the status of an application may be obtained from the Patent

Application Information Retrieval (PAIR) system. Status information for published applications

may be obtained from either Private PAIR or Public PAIR. Status information for unpublished

applications is available through Private PMR only. For more information about the PAIR

system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR

system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

John S. Chu

Primary Examiner, Group 1700

J.Chu

September 30, 2005